

ABSTRACT

The invention includes methods of making lithography photomask blanks.

The invention also includes lithography photomask blanks and preforms for producing lithography photomask. The method of making a lithography photomask

- 5 blank includes providing a soot deposition surface, producing SiO<sub>2</sub> soot particles and projecting the SiO<sub>2</sub> soot particles toward the soot deposition surface. The method includes successively depositing layers of the SiO<sub>2</sub> soot particle on the deposition surface to form a coherent SiO<sub>2</sub> porous glass preform body comprised of successive layers of the SiO<sub>2</sub> soot particles and dehydrating the coherent SiO<sub>2</sub> glass preform
- 10 body to remove OH from the preform body. The SiO<sub>2</sub> is exposed to and reacted with a fluorine containing compound and consolidated into a nonporous silicon oxyfluoride glass body with parallel layers of striae. The method further includes forming the consolidated silicon oxyfluoride glass body into a photomask blank having a planar surface with the orientation of the striae layer parallel to the photomask blank planar surface.